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| Session Title: | [ThE1] Advanced Etching and Monitoring |
| Session Date: | November 14 (Thu.), 2024 |
| Session Time: | 09:00-10:00 |
| Session Room: | Room E (Sicily Room, 1F, Paradise Hotel Busan) |
| Session Chair: | Prof. Won-Jun Lee (Sejong Univ., Korea) |

[ThE1-1]

09:00-09:20

Ideal Si Etching with Ultra-Low Electron Temperature CF₄ Plasma

Junyoung Park, Nayeon Kim, Jung-Eun Choi, Min-Seok Kim, and Chin-Wook Chung (Hanyang Univ., Korea)

[ThE1-2]

09:20-09:40

In-situ Plasma Monitoring using Multiple Plasma Information (PI) for SiO₂ Etch Process with CF₄/O₂

Min Ho Kim, Jeong Eun Jeon, and Sang Jeon Hong (Myongji Univ., Korea)

[ThE1-3]

09:40-10:00

Optical Emission Spectroscopy Analysis (Line Ratio Method) Integrated with Electrical Method for Measuring Accurate Plasma Radical Density

Hyeon-Ho Nahm, Jeong-Hyun Lee, and Chung Chin Wook (Hanyang Univ., Korea)